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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/632,289	08/01/2003	Samuel Pearlman	PU 010211 CIP	5075	
	7590 12/14/2004		EXAM	EXAMINER	
THOMSON MULTIMEDIA LICENSING INC JOSEPH S TRIPOLI			MCPHERSO	MCPHERSON, JOHN A	
PO BOX 5312			ART UNIT	PAPER NUMBER	
2 INDEPENDI PRINCETON,	ENCE WAY' NJ 08543-5312		1756		

Please find below and/or attached an Office communication concerning this application or proceeding.

			_	#1
	•	Application No.	Applicant(s)	U'
Office Action Summary		10/632,289	PEARLMAN ET AL.	
		Examiner	Art Unit	
		John A. McPherson	1756	
Period fe	The MAILING DATE of this communication app or Reply	pears on the cover sheet with the	correspondence address	
THE - Exte after - If the - If NC - Failt Any	MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. In period for reply specified above is less than thirty (30) days, a reply of period for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing led patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be y within the statutory minimum of thirty (30) d vill apply and will expire SIX (6) MONTHS fro	timely filed ays will be considered timely. m the mailing date of this communication JED (35 U.S.C. & 133)	on.
Status				
1)🖂	Responsive to communication(s) filed on 20 No	ovember 2003.		
2a)□		action is non-final.		
3)□	Since this application is in condition for allowar closed in accordance with the practice under E			s
Disposit	ion of Claims			
5)□	Claim(s) <u>1-20</u> is/are pending in the application. 4a) Of the above claim(s) is/are withdraw Claim(s) is/are allowed. Claim(s) <u>1-8 and 13-20</u> is/are rejected. Claim(s) <u>9-12</u> is/are objected to. Claim(s) are subject to restriction and/or	vn from consideration.		
Applicat	ion Papers			
	The specification is objected to by the Examine			
10)⊠	The drawing(s) filed on <u>01 August 2003</u> is/are:			
	Applicant may not request that any objection to the		• , .	
11)	Replacement drawing sheet(s) including the correction The oath or declaration is objected to by the Ex			d).
Priority ι	ınder 35 U.S.C. § 119			
a)[Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau See the attached detailed Office action for a list of	s have been received. s have been received in Applica ity documents have been receiv (PCT Rule 17.2(a)).	tion Noved in this National Stage	
Attachment	t(s) e of References Cited (PTO-892)	, 	·	
2) 🔲 Notic	e of Draftsperson's Patent Drawing Review (PTO-948)	4) 🔲 Interview Summar Paper No(s)/Mail [,
3) 🔲 Inforn	nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date		Patent Application (PTO-152)	

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DETAILED ACTION

Specification

1. The specification is objected to as failing to provide proper antecedent basis for the claimed subject matter. See 37 CFR 1.75(d)(1) and MPEP § 608.01(o). Correction of the following is required: the specification does not provide basis for the subject matter of claims 16 and 17.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-8 and 13-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 6,013,400 to LaPeruta et al. (LaPeruta) in view of EP 0 146 226 (EP '226). LaPeruta discloses a method of manufacturing a luminescent screen with a light absorbing matrix, comprising the steps of exposing a first photoresist through a color selection electrode to light from at least two positions located symmetrically relative to a central source position, developing the first photoresist layer, overcoating with a light absorbing material, removing the remaining photoresist and the light absorbing material thereon to form first guardbands, and repeating the process twice more, using second and third photoresist layers and at least two asymmetrically located light source positions, to produce second and third guardbands (see the abstract and

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column 5, line 57 to column 7, line 51). Additionally, LaPeruta teaches utilizing a tension focus mask as the color selection electrode, wherein the tension focus mask has a similar mask pitch, strand width and slot width as in the present invention. See column 5, lines 16-45 and column 8, lines 14-29. Therefore, the color selection electrode would have a similar transmission as set forth in claim 20 (as opposed to a conventional shadow mask with an area of the openings of about 18-22% of the area of the mask, see column 1, line 62 to column 2, line 7). However, LaPeruta does not disclose additionally exposing each photoresist from an inner source position, such that each photoresist is exposed from three source positions.

EP '226 discloses a "three light source exposure method" for forming black stripes on a panel of a cathode ray tube, wherein each of three photoresist layers are exposed from three positions, namely the reference position O (corresponding to the inner source position of the present invention) and two offset lateral positions Q_1 and Q_2 (see the abstract and page 5, line 31 to page 6, line 11). Furthermore, EP '226 teaches that the "three light source method" is an improvement over a "two light source method" comprising exposing only from positions Q_1 and Q_2 which are laterally offset in opposite directions from the reference position O (see page 2, line 13 to page 3, line 8), because in the "two light source method" the superimposed transmission light intensity distribution is not optimized (see Figure 3 for the "two light source method" distribution, as compared to the "three light source method" distribution of Figure 5).

It would have been obvious to one skilled in the requisite art to utilize an additional exposure from the reference position, as taught by EP '226, in the process of

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LaPeruta because it is taught that utilizing a third exposure from the reference position provides for an optimized light intensity distribution when forming a light absorbing matrix on the faceplate of a cathode ray tube by the lift-off method.

Allowable Subject Matter

- 3. Claims 9-12 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to John A. McPherson whose telephone number is (571) 272-1386. The examiner can normally be reached on Monday through Friday, 8:00 AM to 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

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you have questions on access to the Private PAIR system, contact the Electronic

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John A. McPherson **Primary Examiner** Art Unit 1756

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